

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: HAGIWARA, et al.  
Filed: January 14, 2000  
For: PATTERN FORMING PROCESS USING PHOTSENSITIVE  
RESIN COMPOUND

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3-7-0

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

January 14, 2000

Sir:

Please amend the above-identified application, prior to examination thereof, as follows:

IN THE SPECIFICATION

Please amend the specification as follows:

Page 2, line 1, insert -- is a Divisional application of application Serial No. 09/136,610, filed August 20, 1998, which -- after "application" (first occurrence).

REMARKS

Applicants have amended the specification of the above-identified application, prior to examination thereof, to satisfy the requirements of 35 USC 120 in referring to, inter alia, the immediately prior application of the above-identified application upon which priority is claimed under 35 USC 120. It is respectfully submitted that this amendment of the specification does not add new matter to the application.